Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	8928	(356/300-334,402-425,72-73).CCLS.	US-PGPUB; USPAT; DERWENT	OR	OFF	2005/09/01 17:03
L2	52	1 and (monitor$ detect$ determin$ measur$) near4 (erosion erod$4 wear)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/09/01 17:06
L3	6801	(250/281-300,458.1-461.2).CCLS.	US-PGPUB; USPAT; DERWENT	OR	OFF	2005/09/01 17:06
L4	23	3 and (monitor$ detect$ determin$ measur$) near4 (erosion erod$4 wear)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/09/01 17:07
L5	19454	(monitor$ detect$ determin$ measur$) near4 (erosion erod$4 wear)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/09/01 17:10
L6	244	5 and gas near4 (emit$4 indicat$)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/09/01 17:10
L7	23	6 and (wafer semicondutor) near3 (process$4)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/09/01 17:09
L8	29	6 and (wafer semicondutor) and plasma	US-PGPUB; USPAT; DERWENT	OR	ON	2005/09/01 17:11
L9	19	audunn near ludviksson	US-PGPUB; USPAT; DERWENT	OR	ON	2005/09/01 17:09
L10	7	audunn near ludviksson	EPO; JPO	OR	ON	2005/09/01 17:10
L11	18	Steven near fink	EPO; JPO	OR	ON	2005/09/01 17:10
L12	49	Steven near fink	US-PGPUB; USPAT; DERWENT	OR	ON	2005/09/01 17:10
L13	2275	(monitor$ detect$ determin$ measur$) near4 (erosion erod$4 wear)	EPO; JPO	OR	ON	2005/09/01 17:10
L14	1	13 and gas near4 (emit$4 indicat$)	EPO; JPO	OR	ON	2005/09/01 17:10
L15	1	13 and (wafer semicondutor) and plasma	EPO; JPO	OR	ON	2005/09/01 17:11